Balanced Optimization of 1310 nm Tunnel-Junction VCSELs

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- 3. Numerical Analysis
- 4. Design Optimization
- 5. Summary



VCSEL Design







Advantage

- reduced p-region
- less absorption
- lower resistance
- no p-p bonding



Device	Aperture size	gain-mode offset
A	8 µm	66 nm
В	12 µm	51 nm
С	8 µm	51 nm



larger offset allows for higher lasing temperatures but less gain / power at room temperature





(A) T_{max}=134°C - highest ever achieved with long-wavelength VCSELs



8 µm aperture

• gain-mode offset = 66 nm



(B) lower offset gives ~2 mW room temperature output power



- 12 µm aperture
- Diff. Quantum Eff. = 30%

- gain-mode offset = 51 nm
- Device operation to 100°C



(C) lower aperture gives ~1 mW single mode output power at 66°C



- 8 µm aperture
- Device operation to 123°C

- gain-mode offset = 51 nm
- > 30dB side-mode suppression



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PICS3D: Self-Consistent VCSEL Model



[J. Piprek, Semiconductor Optoelectronic Devices – Introduction to Physics and Simulation, Academic Press, San Diego, 2003]

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Comparison to measurements: PL





Auger recombination rate See 9 9 9 1nGaAsP InAsSb nSb nAs nGaSb InP GaAs $R_{Aug} = (C_n n + C_p p)(np - n_i)$ 1x10⁻²³· literature overview 1x10⁻²⁴ $C(20^{\circ}C) = 1.15 \times 10^{-29} cm^{-6} s^{-1}$ (m) 1x10⁻²⁵ 1x10⁻²⁶ 1x10⁻²⁷ 1x10⁻²⁷ 1x10⁻²⁸ 1x10⁻²⁹ 1x10⁻³⁰ 1x10⁻²⁵ = $C(T) = C_0 \exp\left[-\frac{160meV}{kT}\right]$ 1x10⁻²⁶ 1x10⁻²⁸ Defect recombination lifetime MQW $\tau_{SRH} = 10 ns$ 1x10⁻³¹ elsewhere $\tau_{SRH} = 100 ns$ 0.2 0.4 0.6 0.8 1.4 0.0 1.0 1.2



Intervalenceband and free carrier absorption

 $\alpha_{fc} = k_p p + k_n n$ $k_p = 13 \times 10^{-18} \text{cm}^2$ $k_n = 2 \times 10^{-18} \text{cm}^2$

Background absorption (fit) $\alpha_{\rm b} = 3 / \rm{cm}$

Band offset
$$\Delta E_c / \Delta E_g = 0.72$$
for AlGaInAs $\Delta E_c = 292 \text{ meV}, \Delta E_v = 147 \text{ meV}$ for InP/AlInAsBand shift $dE_q/dT = 334 \text{ meV/K}$ as measured

as measured



fit parameter: DBR thermal conductivity k_{DBR}

















- 1. Reduce leakage, enhance slope efficiency
- 2. Reduce bias, limit self-heating
- 3. 1 mW single mode power at 80°C

Optimization: Remove n-side AllnAs Layer



UCSB



Optimization: Higher n-Doping





Optimum offset for maximum power = 32 nm (original: 51 nm)





Optimum number of top DBR periods = 28 (original: 27)





Optimum number of quantum wells = 5 (original)





Overall Design Optimization

- remove n-AllnAs layer
- gain offset 51 => 32 nm
- tunnel-junction doping x 2
- tunnel-junction aperture 8 =>10µm
- n-InP regrowth doping x 4
- top DBR periods: 27 => 28





Intrinsic modulation response for optimized design





balanced design optimization enables

- high temperature (80°C)
- high power (> 1 mW)
- high-speed ($f_r > 20 \text{ GHz}$)
- single fundamental mode lasing
- using self-consistent numerical model
- including careful parameter calibration
- agreement with original device measurements

Future: include many-body gain